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## CERTIFICATE OF FACSIMILE TRANSMISSION

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Janice O'Harris

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PATENT

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

David Becker et al.

Group Art Unit: 1763

Serial No.: 09/923,058

Examiner: unk

Filed: August 6, 2001

Atty. Dkt. No.: MCRO284—2/LWT

For: METHODS FOR ENHANCING SILICON  
DIOXIDE TO SILICON NITRIDE  
SELECTIVITY (AS AMENDED HEREIN)

PRELIMINARY AMENDMENT

Assistant Commissioner for Patents  
Washington, D.C. 20231

Please consider the enclosed preliminary amendment. Applicant has brought the total number of claims in the application to 94, but only three independent claims are now pending. Hence it is believed that the Applicant owes this office  $(94 - 20) * \$18.00 = \$ 1,332.00$  in connection with this filing. The Assistant Commissioner is authorized to deduct this fee, or any other fees that are due in connection with this response or otherwise, to Deposit Account No. 01-2508/MCRO284--2/LWT.

Reconsideration of the application is respectfully requested.

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## I. AMENDMENTS

- Please change the title of the application to the following:

-- METHODS FOR ENHANCING SILICON DIOXIDE TO SILICON NITRIDE SELECTIVITY --

- Please replace the abstract with the following paragraph:

— A process for controlling the plasma etch of a silicon dioxide layer at a high etch rate and high selectivity with respect to silicon nitride, particularly in a multilayer structure, by (1) maintaining various portions of the etch chamber at elevated temperatures, and/or (2) using an etch chemistry having a fluorohydrocarbon gas containing at least as many hydrogen atoms as fluorine atoms, preferably CH<sub>2</sub>F<sub>2</sub> or CH<sub>3</sub>F. --

- Please replace the specification paragraph beginning at page 1, line 4 with the following paragraph:

-- This is a continuation application of co-pending U.S. Application Serial Number 09/344,277, filed June 30, 1999, which issued as U.S. Patent Number 6,287,978 on September 11, 2001; which was a continuation of U.S. Applicant Serial Number 08/905,891, filed August 4, 1997, which issued as U.S. Patent Number 6,015,760 on January 18, 2000; which was a continuation of U.S. Application Serial Number 08/152,755, filed November 15, 1993, which issued as U.S. Patent Number 5,880,036 on March 9, 1999; which was a continuation-in-part of U.S. A[a]pplication Serial Number 07/898,505, filed June 15, 1992, which issued as U.S. Patent Number 5,286,344 on February 15, 1994. --